

Electronic Supplementary Information

Experimental Section

Materials: Copper nitrate trihydrate, 1,4-benzenedicarboxylic acid (TPA), N,N-dimethylformamide (DMF) were purchased from Aladdin Ltd. (Shanghai, China). $\text{RuCl}_3 \cdot 3\text{H}_2\text{O}$ ($\geq 43\%$) were bought from Sigma-Aldrich Chemical Reagent Co., Ltd. Nickel foam (NF) was supplied by Changsha Liyuan New Material Ltd, which was washed with acetone, hydrochloric acid (3 mol/L), ethanol and deionized water several times to remove the surface impurities. Ultrapure water (18.2 M Ω .cm) was utilized to prepare all solutions. All reagents were used as received without further purification.

Preparation of NiCu-MOFNs/NF

Ni-Cu MOFNs was grown on the Ni foam through one-pot hydrothermal synthesis: copper nitrate trihydrate 1 mmol (0.242 g) and 1,4-benzenedicarboxylic acid 1mmol (0.166g) were dissolved in 35 mL DMF under constant stirring for 30 min. The final solution and the pre-treated Ni foam (2cm *3cm) were sealed in a 40 mL Teflon-lined stainless-steel autoclave and maintained at 110 °C for 36 h, followed by slow cooling to room temperature. The product was washed for three times with DMF, deionized water and ethanol successively. Dried under 60 °C in air for 4 hours.

Synthesis of RuO₂

RuO₂ was prepared according to previous publication. Briefly, 1.5 g of $\text{RuCl}_3 \cdot 3\text{H}_2\text{O}$ was added into 50 mL distilled water and stirred for ten minutes. Then 15.0 mL KOH (1.0 M) was added and stirred for 45 min at 100 °C. The above solution was centrifuged for 10 minutes and filtered. The precipitates were collected and washed with pure water several times. Finally, the product was dried at 80 °C overnight and then annealed at 300 °C in air atmosphere for 3 h. For a typical synthesis of RuO₂/NF electrode, 50 mg RuO₂ was dispersed in 1 mL ethane/water (v:v = 1:1) solution with sonication for 30 min. Then 21 μL catalytic inks were dropped on Ni foam (0.5 × 0.5 cm), and dried at 80 °C for 4 h. The loading for RuO₂/NF was about 4.2 mg cm⁻².

Characterizations

X-ray diffraction (XRD) measurements were using a RigakuD/MAX 2550 diffractometer with Cu K α radiation ($\lambda=1.5418 \text{ \AA}$). Samples were analyzed over a range of 5–80° using a step scan mode with a step rate of 4°/min. SEM measurements were carried out on a MERLIN Compact scanning electron microscope at an accelerating voltage of 20 kV. TEM images were collected on a Zeiss Libra 200FE transmission electron microscope operated at 200 kV. XPS measurements were performed using an ESCALABMK II X-ray photoelectron spectrometer with the exciting source of Mg. FT-IR measurement was carried out on Nicolet Nexus 410 spectrometer. ICP-OES was performed using an Agilent Icpoes730 spectrometer.

Electrochemical measurements

All the electrochemical measurements are performed with a CHI 660E electrochemical analyzer (CH Instruments, Inc., Shanghai) at room temperature in a conventional three electrode system, using NiCu-MOFNs/NF as working electrode, graphite rod as counter electrode and mercuric oxide electrode (Hg-HgO) electrode as reference electrode. All tests were carried out at room temperature (25 °C)

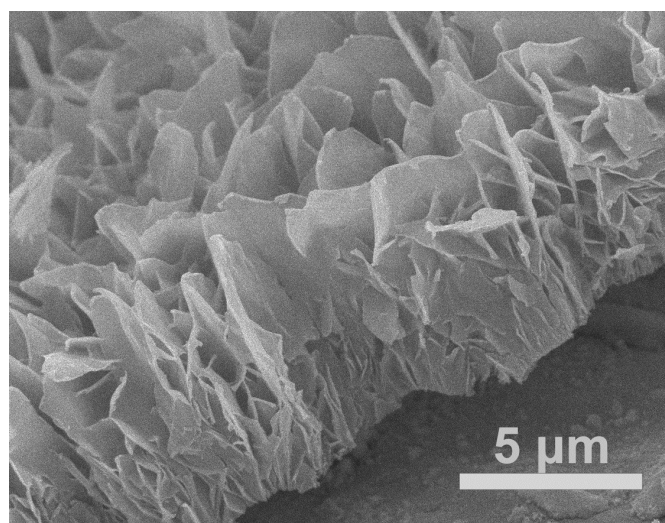


Fig. S1. SEM pattern of NiCu-MOFNs/NF

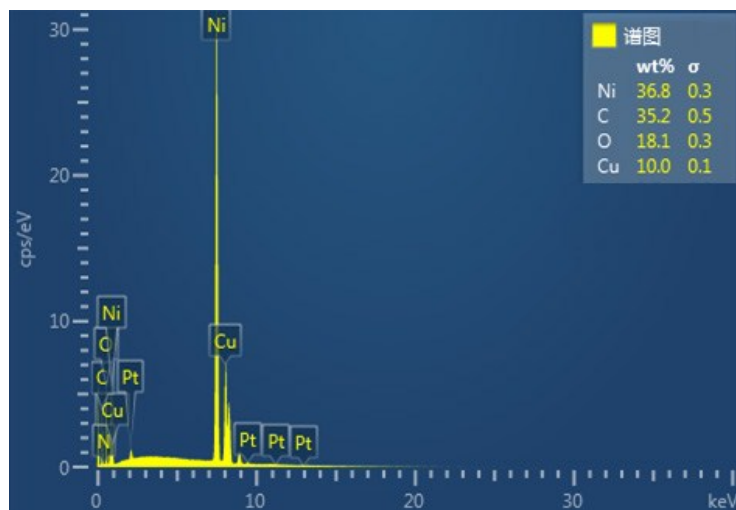


Fig. S2. EDX spectrum of NiCu-MOFNs.

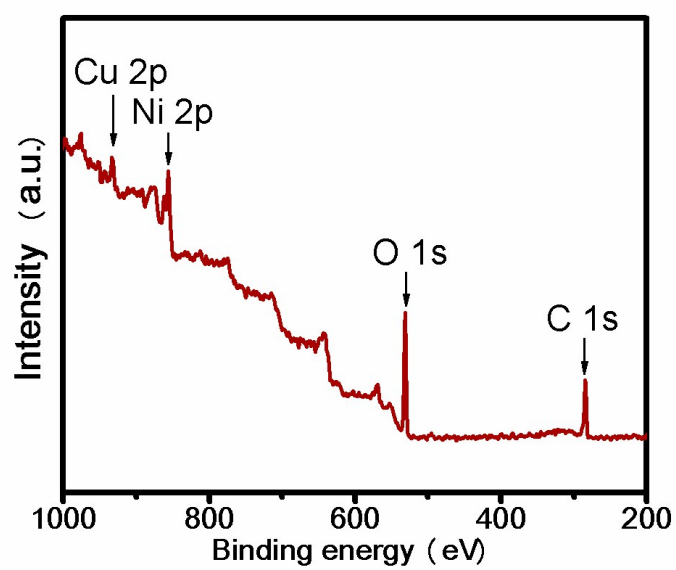


Fig. S3. XPS spectra of NiCu-MOFNs

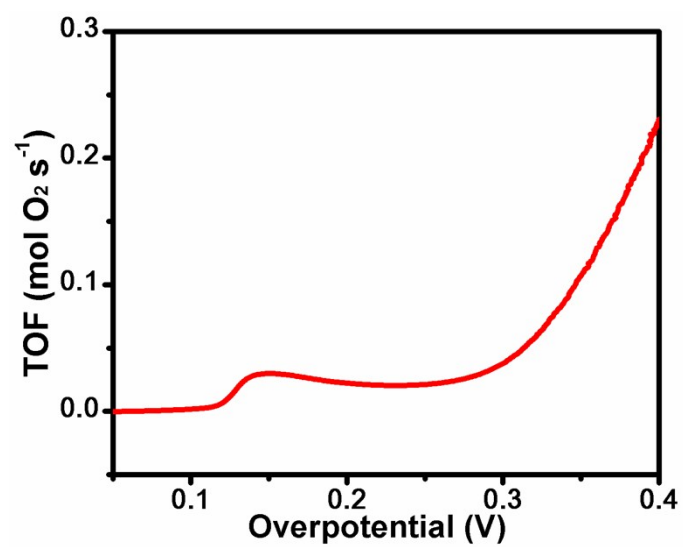


Fig. S4. Plot of TOF for NiCu-MOFNs/NF

Table S1: ICP-OES data for NiCu-MOFNs powder scratched from NiCu-MOFNs/NF

Mass of sample/g	Volume/ml	Metal	Concentration in solution (mg/L)	Concentration (mg/g)	Concentration (mol/g)
0.0138	250	Ni	13.54	245.29	0.00418
		Cu	3.471	62.88	0.00099

Table S2. Comparison of OER performance for NiCu-MOFNs/NF with other non-noble-metal electrocatalysts in alkaline media.

Catalyst	j (mA cm ⁻²)	η (mV)	Electrolyte	Ref.
NiCu-MOF/NF	100	309	1.0M KOH	This work
NiFe-MOF/NF	10	240	1.0M KOH	1
NiCo-MOF/CF	10	189	1.0M KOH	2
(GO 8 wt%) Cu-MOF/GC	2	110	0.5M H ₂ SO ₄	3
NiS/Ni foam	100	350	1.0 M KOH	4
Ni-P/Ni	100	374	1.0 M KOH	5
Zn _x Co _{3-x} O ₄ nanowire array	50	390	1.0 M KOH	6
NiFe LDH/NF	100	390	1.0 M KOH	7
Ni ₃ Se ₂ /Cu foam	100	388	1.0 M KOH	8
NiFe/NF	20	264	1.0 M KOH	9
Cu ₃ P@NF	10	320	1.0 M KOH	10
Co ₃ O ₄ /NiCo ₂ O ₄	10	340	1.0 M KOH	11
NiCo-NS	10	334	1.0 M KOH	12
CeO ₂ /CoSe ₂	10	288	0.1 M KOH	13
Al-CoP/CC	10	265	1.0 M KOH	14
Cu/(Cu(OH) ₂ -CuO) NA/CF	10	390	1.0 M KOH	15
carbonate-Co(OH) ₂ /NF	50	337	1.0 M KOH	16
Fe-CoP/CC Fe-CoP/CC	10	340	1.0 M KOH	17
Ni ₃ Se ₂ /CF Ni ₃ Se ₂ /CF	10	420	1.0 M KOH	18
Co ₃ O ₄ /N -rmGO	10	310	1.0 M KOH	19
Co ₃ O ₄ @C-MWCNTs	10	320	1.0 M KOH	20

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